

Freeform Search

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IBM Technical Disclosure Bulletins

Term: 110 and (acid or acidic or ph) with (silica or silicon or "sio.sub.2" or sio2 or abrasive) and (basic or alkali or ph) near substance

Display: 10 **Documents in Display Format:** - **Starting with Number** 1

Generate: ☐ Hit List ☒ Hit Count ☐ Side by Side ☐ Image

Search

Clear

Interrupt

Search History

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<u>Set</u> <u>Name</u>	<u>Query</u>	<u>Hit</u> <u>Count</u>	<u>Set</u> <u>Name</u> result set
side by side			
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<u>L14</u>	110 and (acid or acidic or ph) with (silica or silicon or "sio.sub.2" or sio2 or abrasive) and (basic or alkali or ph) near substance	7	<u>L14</u>
<u>L13</u>	112 not 111	17	<u>L13</u>
<u>L12</u>	110 and (acid or acidic or ph) with (silica or silicon or "sio.sub.2" or sio2 or abrasive) and (basic or alkali or ph) near solution	59	<u>L12</u>
<u>L11</u>	110 and (acid or acidic or ph) near4 (silica or silicon or "sio.sub.2" or sio2 or abrasive) and (basic or alkali or ph) near solution	42	<u>L11</u>
<u>L10</u>	bulk density and (fumed or fume) (silica or silicon or "sio.sub.2" or sio2) and (polishing or planarizing or planarization or abrasive or cmp or polish)	264	<u>L10</u>
<u>L9</u>	L8 and bulk density	2	<u>L9</u>
<u>L8</u>	L7 and (fumed or fume) (silica or silicon or "sio.sub.2" or sio2)	95	<u>L8</u>
<u>L7</u>	(acid or acidic or ph) near4 silica and (polishing or planarizing or planarization or abrasive or cmp or polish).ti. and (basic or alkali or ph) near solution	247	<u>L7</u>
<i>DB=PGPB,USPT; PLUR=YES; OP=ADJ</i>			
<u>L6</u>	13 and 15	0	<u>L6</u>

<u>L5</u>	5116535.pn. or 5246624.pn. or 6248144.pn. or 6409780.pn.	4	<u>L5</u>
<u>L4</u>	20020028636 or 20040040217 or 5116535.pn. or 5246624.pn. or 6248144.pn. or 6352679.pn. or 5904159.pn.	7	<u>L4</u>
<u>L3</u>	(acid or acidic) near4 silica and (polishing or planarizing or planarization or abrasive or cmp or polish).ti. and (basic or alkali) solution	32	<u>L3</u>
	<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>		
<u>L2</u>	L1 and (acid or acedic) fumed silica	1	<u>L2</u>
<u>L1</u>	(polishing or planarizing or planarization or abrasive or cmp or polish).ti. and (abrasive or silica or silicon dioxide or silicon oxide or (polishing or planarizing or planarization or cmp) (particle or particulate or grit or grain)) with (volume or vol or "vol." or "vol.%" of "vol%") with (size or diameter) with (nm or nanometer)	68	<u>L1</u>

END OF SEARCH HISTORY